# Advanced Packaging Technologies usher in a new era in the semiconductor marketplace

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#### Take aways from this talk

- Advanced packaging technologies will re-enable widespread use of custom semiconductor designs in products worldwide
- S3B is influencing the positioning and growth of semiconductor activities in Australia
- Building and operating advanced packaging plants in Australia
   + Gaining access to semiconductor global supply chain companies
   will make us competitive in mainstream semiconductor and other markets

#### **CAD** Licenses

## Training and Fundamental Research

High license costs and accessibility compared to Europe, North America and Taiwan

Major change for academic licenses following discussions with Cadence:

US Style university program rolled out across country Substantial discounts for teaching and fundamental research purposes

#### Start-ups

Facilitated introductions between start ups and vendors Begun discussions with CAD vendors around start-up programs Idea is to host a pool of licenses accessible to start-ups – promising discussions ongoing

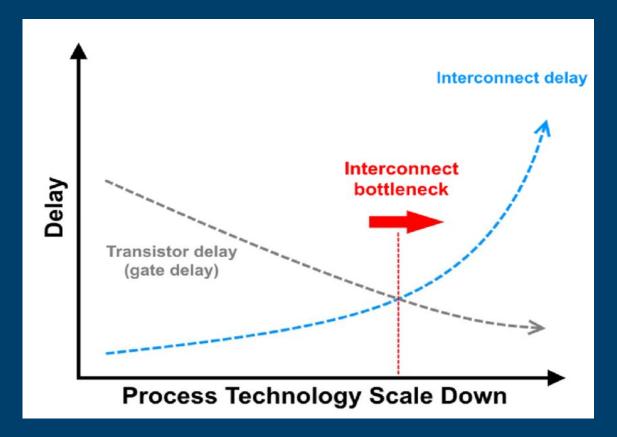


## "

## The number of transistors on a microchip doubles every two years.

- Gordon E Moore

#### Effective End of Moore's Law - Its All About The Wire



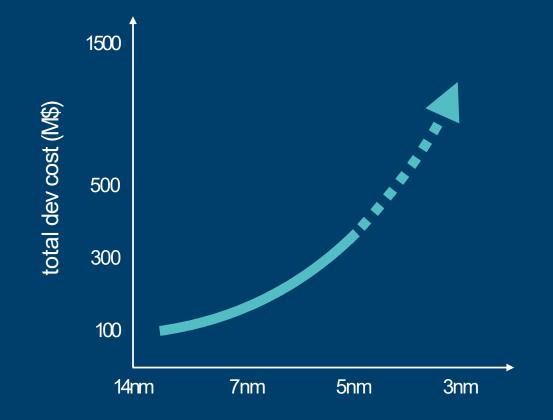


3DInCities

### 3nm Lithography – Jensen Huang – Nvidia CEO

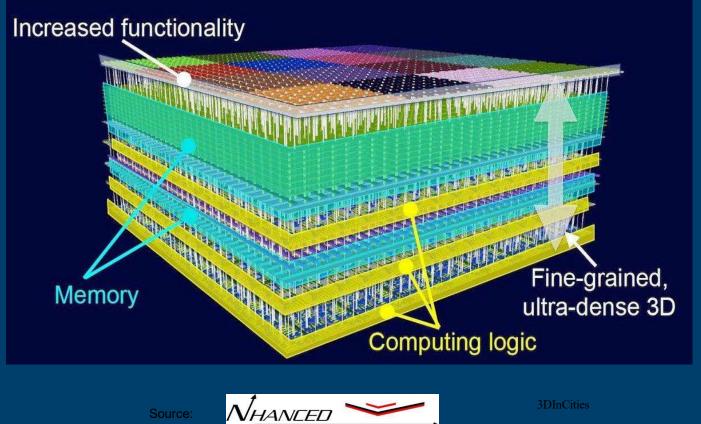


### Soaring cost of chip design



#### 3D packaging - dramatically reduces wire lengths

- 95% of the power
- 98% of the delay



EMICONDUCTORS

## "

It may prove to be more economical to also build large systems out of smaller functions, which are separately packaged and interconnected.

- Gordon E Moore

#### Bob Patti Vision of the Future - Foundry 2.0

A new semiconductor industry paradigm is evolving... A Finishing Foundry that takes the standardized building blocks from traditional semiconductor manufacturers and uses advanced packaging and additive manufacturing to create highly customized components with superior performance targeting small and medium sized markets.

(Essentially a semi fab without front-end-of-line)

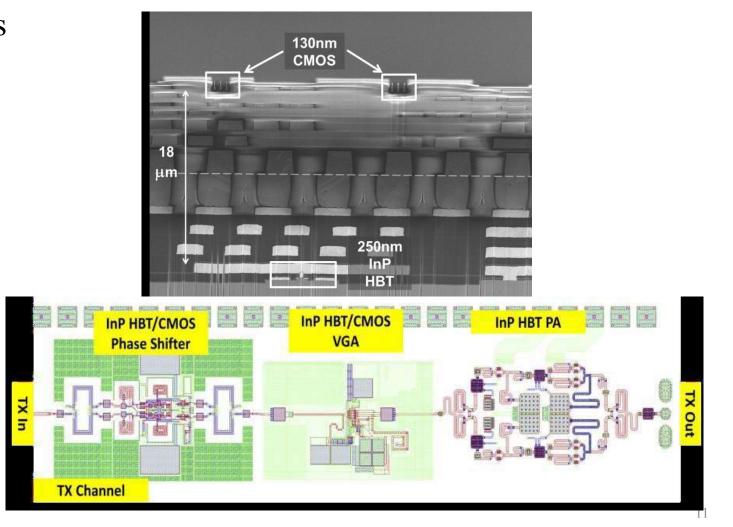


### **AP Elements: Bonding**

Millimeters → Microns

Kilograms ➡ Grams

Mixed Materials Best of Class



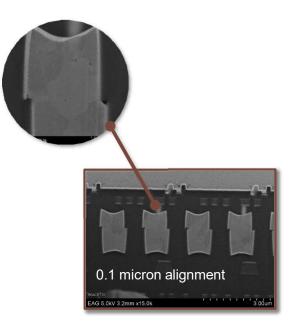
#### A Powerful New Tool: Hybrid Bonding – One of Many

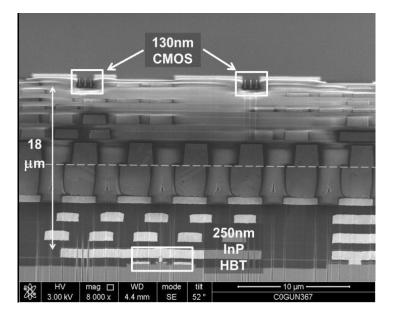
Millimeters → Microns

Kilograms i Grams



Global Foundries top wafer

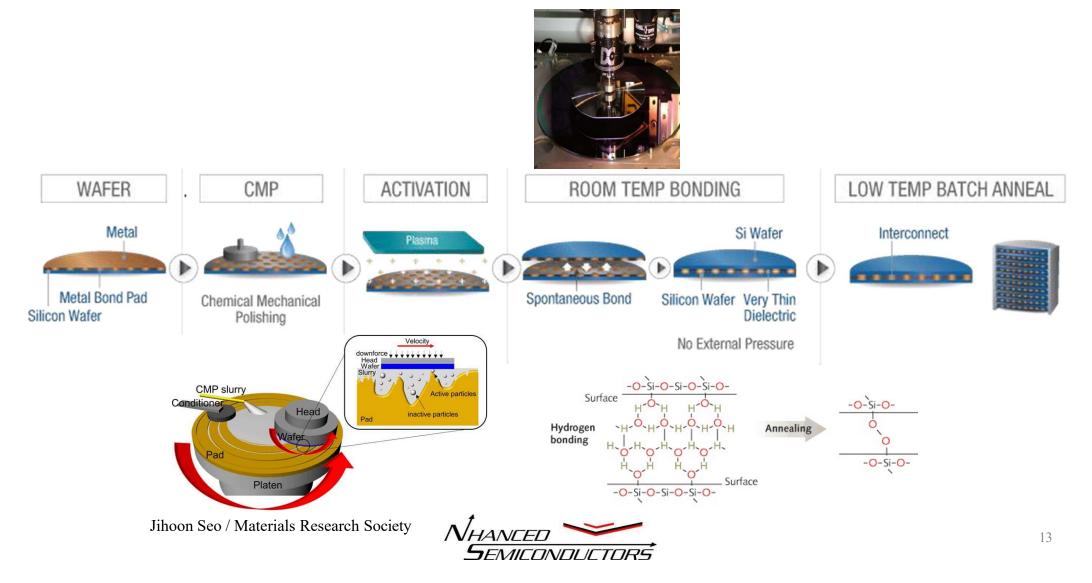


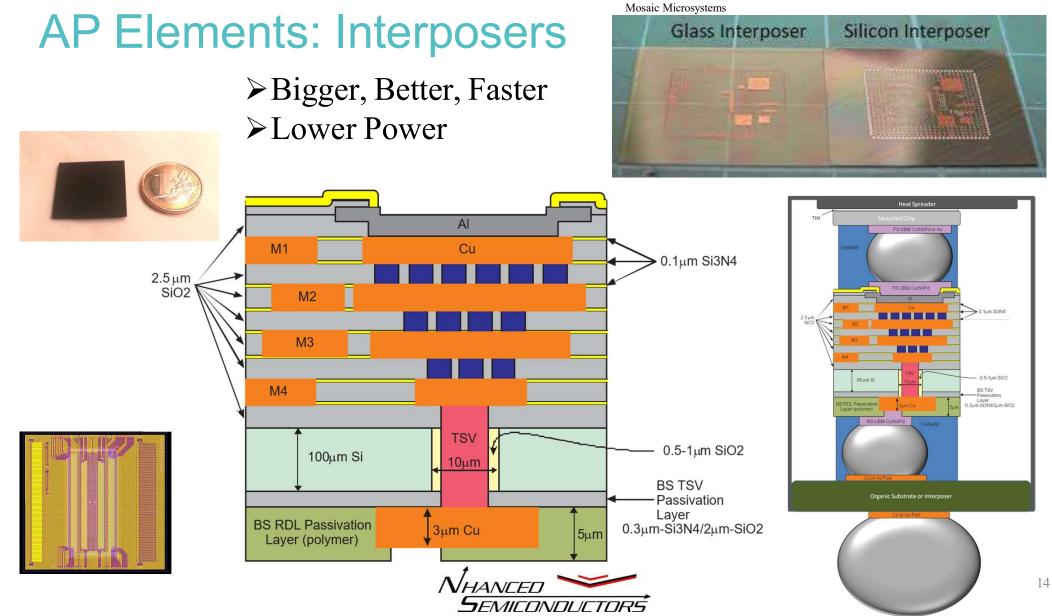


Teledyne InP bottom wafer



#### DBI®: Low Temperature Hybrid Bonding Process

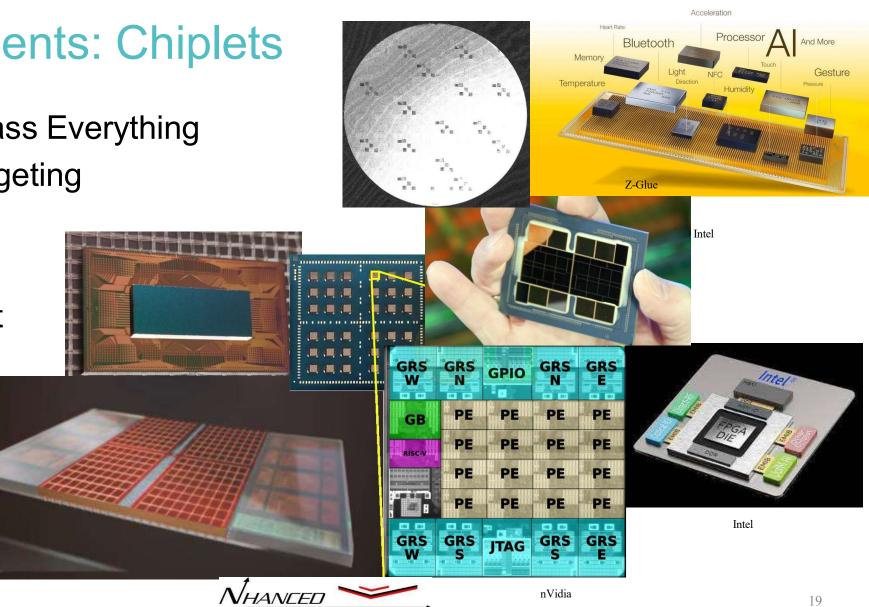




## **AP Elements: Chiplets**

- **Best of Class Everything** •
- Easy retargeting
- Lower risk •
- **IP** reuse •
- Lower cost •

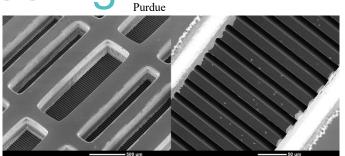
AMD

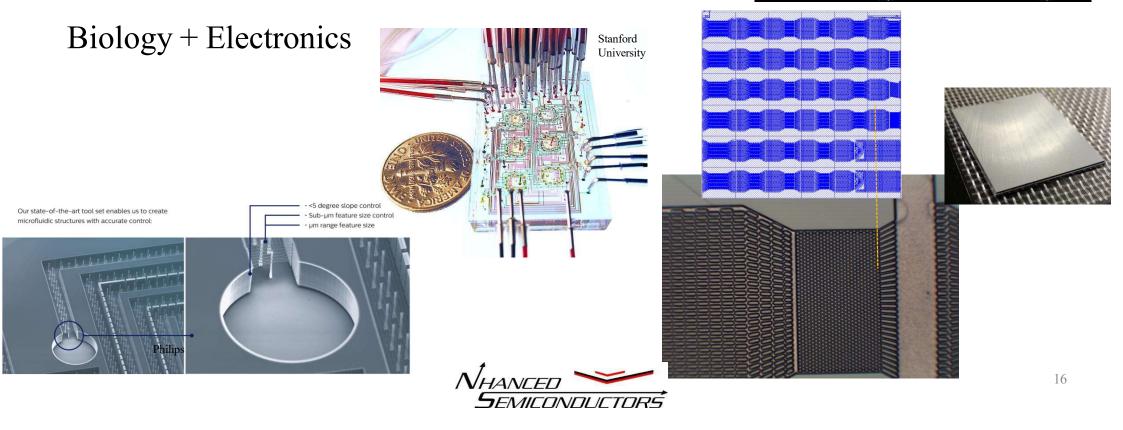


SEMICONDUCTORS

### **AP Elements: Microfluidics and Cooling**

#### Chip Scale Cooling For Ultra-Dense Electronics

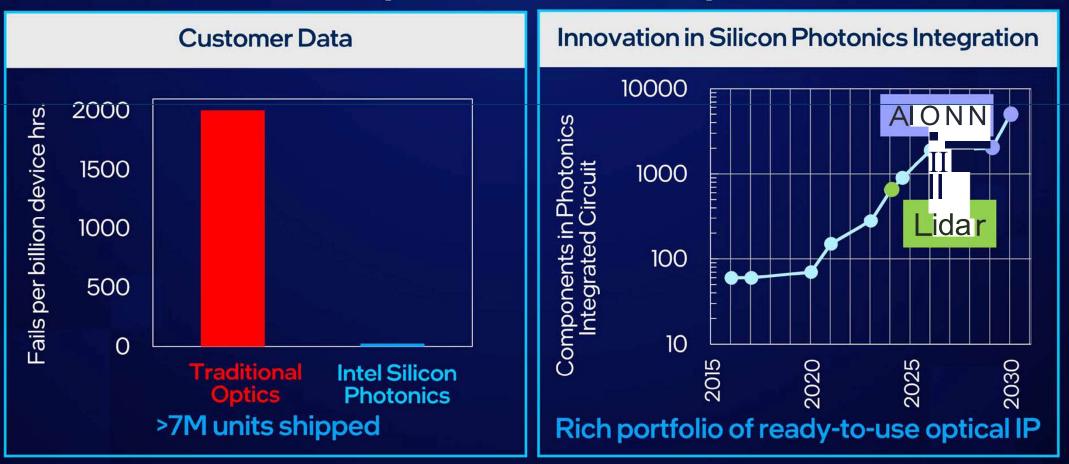




#### Packaging advances to enable Integration of ever-increasing Functionality

Ponte Vecchio, HPC	Blurring the boundary between wafer & package			
<ul> <li>Nodes</li> <li>MIB &amp; Foveros</li> <li>Transistors</li> <li>MiB &amp; Foveros</li> <li>Transistors</li> </ul>	Transient thermal optimization for Performance per Watt gain			
Industry Record for Integration	Industry leading Thermal-Power- Performance Modeling from Transistor to System			

#### Integration of Silicon Photonics improves Reliability



A. Kelleher, IRPS 2023 keynote

#### The need for a more aggressive semiconductor & compute systems roadmap





#### How will we realize this exponential increase?

#### 3D stacking provides linear complexity increase

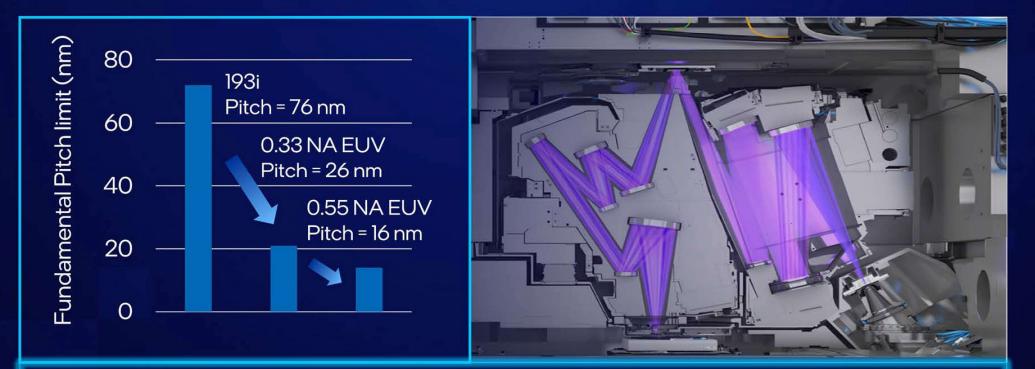
3D stacking provides linear complexity increase 2D scaling provides exponential complexity increase

## Potential roadmap extension

N7	N5	N3	N2	A14	A10	A7	A5	A3	A2	
						Continued dimensional scaling				
Metal Pitch 40 [nm]	28	22	21	18	16	16-14	16-12	16-12	16-12	
Metal Tracks 7	Device and material innovatio Metal Tracks 7 6 6 6 5 5 5 4 <4					vations <4				
m	П	m	E	E		E	B	B		
FinFET	Finfet	Finfet	GAA	GAA	GAA	GAA	CFET	CFET	CFET	
			Nanosheet	Nanosheet	Forksheet	Forksheet	Context-a	ware interc	Atomic	



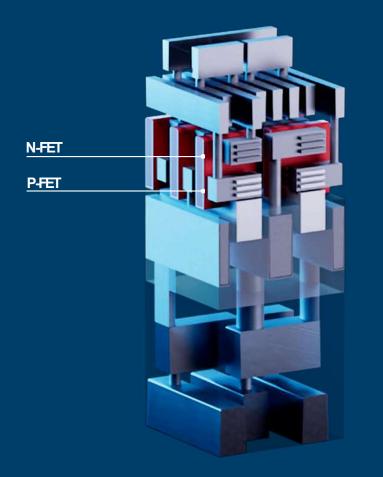
#### High-NA EUV improves resolution to enable further Silicon Technology Scaling



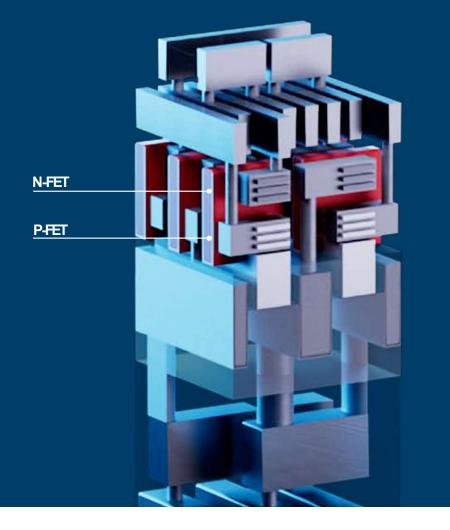
Intel in partnership with ASML will be the first to bring high-NA EUV to high volume manufacturing

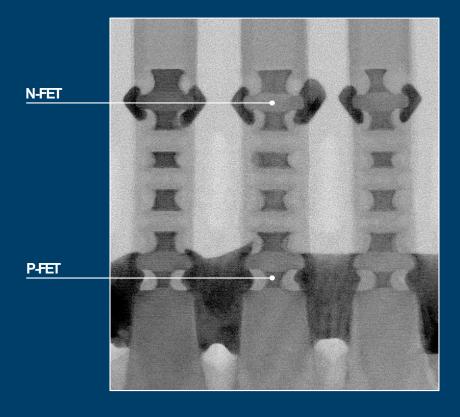
Image from ASML

## Complementary FET (CFET)

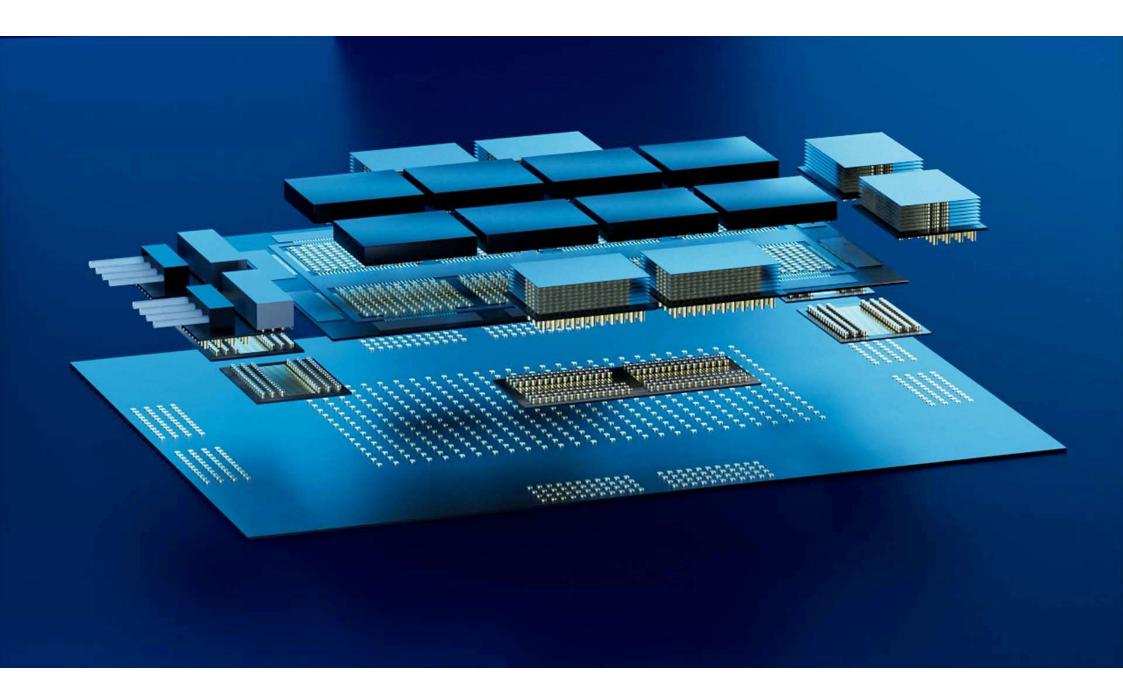


## Complementary FET (CFET)





### We need to combine a multitude of approaches



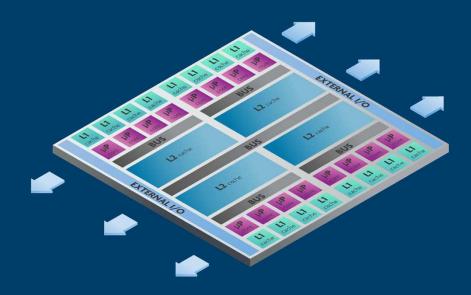


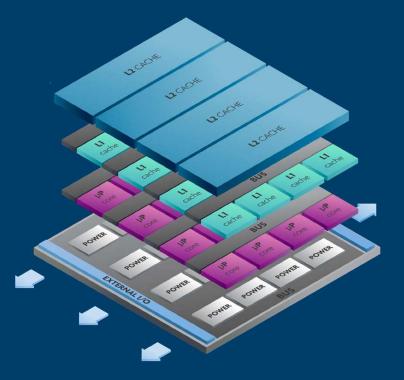






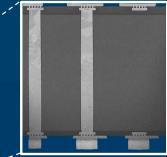




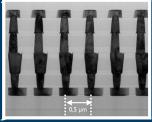


SRAM 2	
SRAM 1	
Drive logic	
Dense logic	
Functional BS	
I/O	

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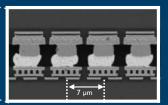




Cu-Cu Hybrid Bonding

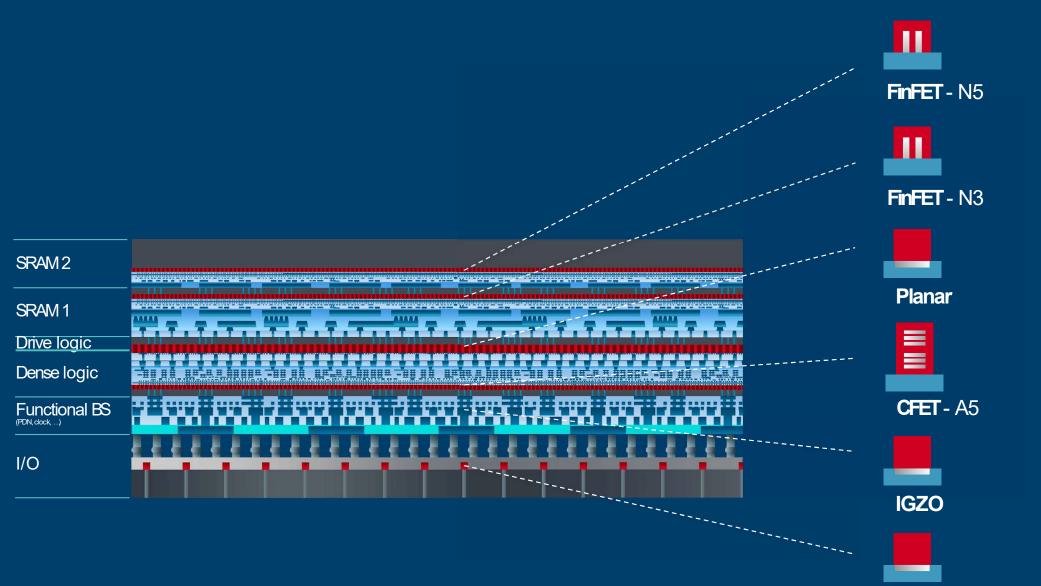


Back-side Power Distribution



D2W using micro-bump

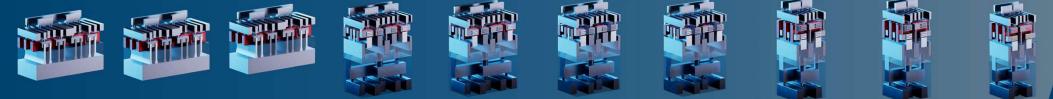
SRAM 2	A A A A A A A A A A A A A A A A A A A
SRAM 1	
Drive logic	
Dense logic	
Functional BS	
I/O	



**Planar** - N28-N14

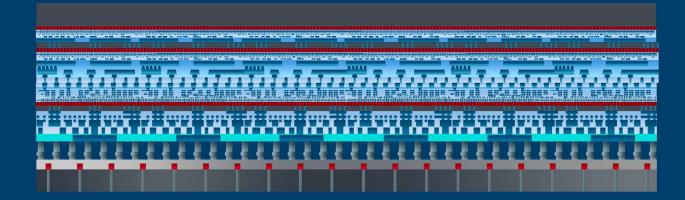
#### Potential roadmap extension

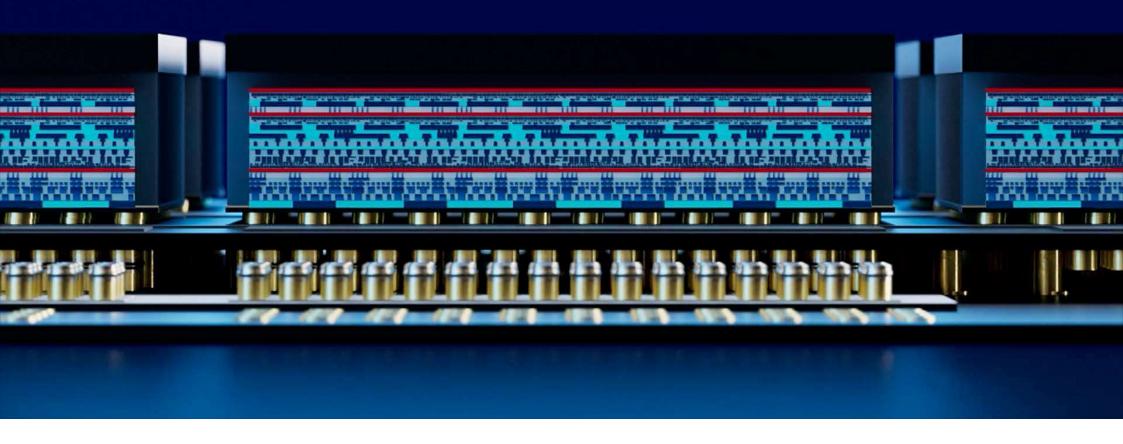
	2018	2020	2022	2024	2026	2028	2030	2032	2034	2036
	N7	N5	N3	N2	A14	A10	<b>A</b> 7	A5	A3	<b>A</b> 2
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								evice and ma	atorial inno	atione
Metal tra	acks 7	6	6	6	5	5	5	4		4
						- <b>-</b>	- <b>1</b> 1			
							E			
	FnFET	FnFET	FNFET	<b>GAA</b> Nanosheet	<b>GAA</b> Nanosheet	<b>GAA</b> Forksheet	<b>GAA</b> Forksheet	CFET	CFET	<b>CFET</b> Atomic
								Context-a	ware interco	onnect



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## Thank You For Being Here!

